

# Silicon–oxygen-bonded oligomers having thermoelectric switching properties

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**The electrical properties of siloxane oligomers prepared from the reaction of 1,4-naphthalenediol or 1,4-naphthoquinone with diphenylsilane using different palladium catalysts, such as  $\text{PdCl}_2$ ,  $\text{Pd}(\text{TMEDA})\text{Cl}_2$ ,  $\text{Pd}(\text{TEEDA})\text{Cl}_2$  (where TMEDA = *N,N'*-tetramethylethylenediamine, TEEDA = *N,N'*-tetraethylethylenediamine), are dependent on the catalyst. Thermoelectric switching properties can be obtained from the siloxane prepared from the coupling reaction of diphenylsilane with 1,4-naphthoquinone or 1,4-naphthalenediol using  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  as catalyst. Copyright © 2001 John Wiley & Sons, Ltd.**

**Keywords:** siloxane; thermoelectric switching; oligomers

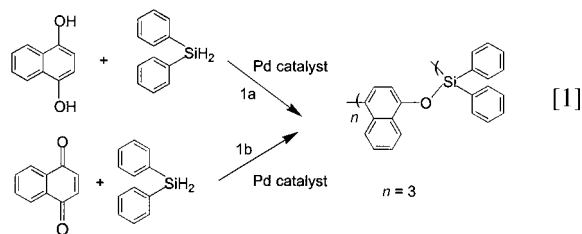
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## INTRODUCTION

Cyclic compounds having multiple aromatic rings, such as calixarene, possess  $\pi$ -interactions and also have capabilities for  $\pi$ -cation interaction.<sup>1,2</sup> Crown ethers also bind to cations and recognize molecules.<sup>3,4</sup> Cyclic siloxanes are also useful in molecular recognition<sup>5–7</sup> and possess properties similar to crown ethers.<sup>8</sup> The siloxanes are usually prepared by substitution reactions on silicon–halogen-bonded compounds,<sup>9,10</sup> dehydrogenative coupling reactions<sup>11</sup> or by reductive coupling reactions of carbonyl compounds with silanes.<sup>12</sup> Dehydrogenative coupling and reductive coupling reactions are catalysed by different metal cata-

lysts.<sup>13–18</sup> Catalytic methods are extensively used in the Si–O-bonded oligomers and palladium catalysts are found to be superior in these reactions.<sup>19</sup> Silicon can form direct metal–silicon bonds<sup>20</sup> and they also form complexes with transition metals through Si–O–metal bonds.<sup>21</sup> There is also a need to understand the products from transition-metal-catalysed reactions of silicon substrates leading to metallacycles.<sup>22</sup> Silicon can expand its valency and can possess five, six or four co-ordination depending on its environment.<sup>23–25</sup> Siloxanes having polynuclear aromatic rings on the main chain are expected to produce interactions through  $\pi$ -stacking. These weak interactions could lead to supramolecular assemblies having novel physicochemical properties.<sup>26</sup> Such properties should be susceptible to thermal effects. This work is concerned with synthesis of siloxanes containing naphthalonic units on the main chain and their thermal properties.

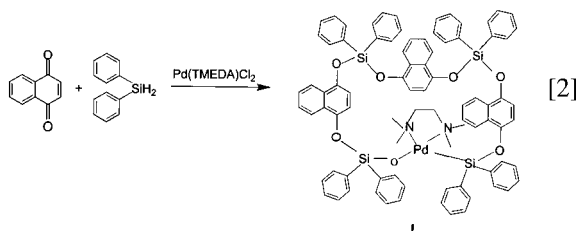
We have recently demonstrated that palladium catalysts are suitable for synthesis of siloxane oligomers.<sup>12</sup> We have extended this to dehydrogenative coupling reactions between diphenylsilane with 1,4-naphthalenediols or with 1,4-naphthoquinone with catalysts such as  $\text{PdCl}_2$ ,  $\text{Pd}(\text{TMEDA})\text{Cl}_2$ ,  $\text{Pd}(\text{TEEDA})\text{Cl}_2$  (where TMEDA = *N,N'*-tetramethylethylenediamine, TEEDA = *N,N'*-tetraethylethylenediamine) (Eqn [1]).



The  $M_n$  values of the oligomers are in the range 3800–4000 with a polystyrene standard. The oligomers are soluble in common organic solvents such as chloroform, dichloromethane, tetrahydrofuran, etc. These oligomers are devoid of Si–H frequencies but possess  $\nu_{\text{OH}}$  frequencies. The Si–

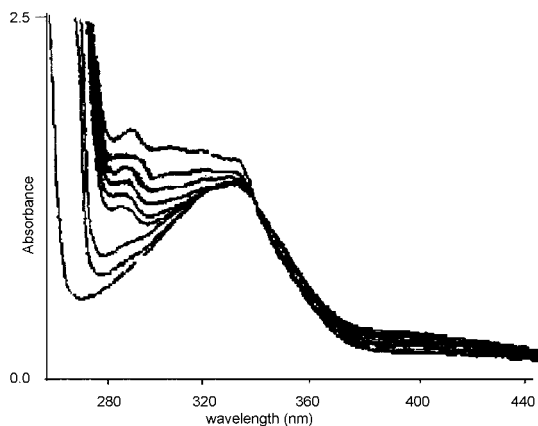
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O frequencies in each of these oligomers appear as strong multiple absorptions in the region 1000–1100  $\text{cm}^{-1}$ . The IR spectra of the oligomers are similar except in the region 1600–1700  $\text{cm}^{-1}$ , where the  $\nu_{\text{OH}}$  overtone vibration occurs. The siloxanes have palladium attached to them. To determine the end group present in the product a representative fast atom bombardment (FAB) mass spectrum of the product obtained from the reaction of 1,4-naphthoquinone with diphenylsilane catalysed by  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  shows it to have the structure **I** (Eqn [2]).



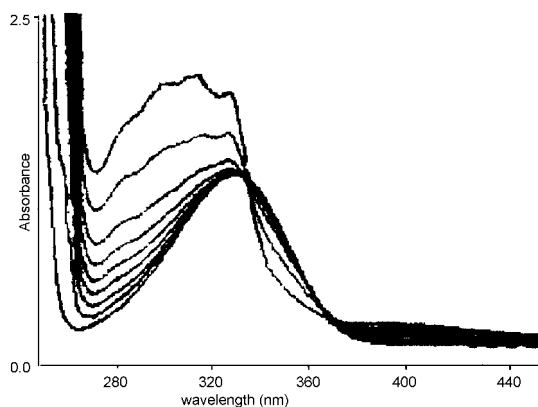
The highest  $m/z$  value in the FAB mass spectrum of **I** is at 1439 and corresponds to four units of diphenylsilane and three naphthalenic units with palladium(II) attached to tetramethylethylenediamine. The  $m/z$  signal at 1439 is a broad spread from 1436–1444 due to the isotopic abundance of palladium. In **I** the palladium is anchored through Si—O—Pd and Si—Pd bonds. These bonds might have formed during the coupling reactions that follow oxygenation of silanes from contaminated water. Examples of such reactions are well documented.<sup>27</sup> The mass spectra could be due to the degradation of the oligomers and may occur due to colloidal palladium formed during the coupling reaction, and trapped in the stacks of the siloxane oligomers.<sup>28,29</sup> Colloidal metal formation during dehydrogenative coupling reactions is well documented. The palladium atoms thus deposited may be responsible for the molecular mass and the FAB mass spectrum. Although in the case of the reaction of diphenylsilane with naphthoquinone catalysed by  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  it has not been possible to obtain an NMR signal from the TMEDA moiety in solution, it is likely that the palladium is loosely bound and precipitates out of the solution.

The visible spectra of a mixture containing 1,4-naphthalenediol with diphenylsilane in the presence of  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  changes with time and shows an isosbestic point at 335 nm (Fig. 1), whereas a similar study on the reaction of diphenylsilane and 1,4-naphthoquinone with  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  shows two isosbestic points, one at 370 nm and another at 335 nm (Fig. 2). The observation of a common

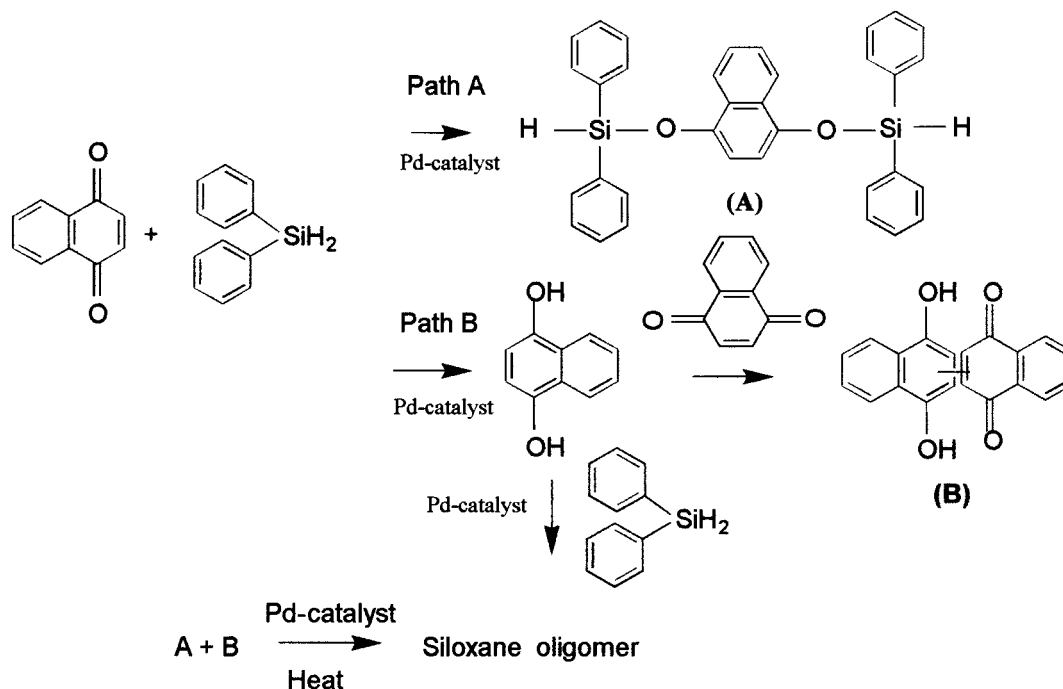


**Figure 1** Change in absorbance during the reaction of 1,4-naphthalenediol (0.1 mmol) with diphenylsilane (0.1 mmol) in the presence of  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  (0.01 mmol) in dichloromethane (3.5  $\text{cm}^3$ ) recorded at 4 min time intervals at 30 °C.

isosbestic point at 335 nm in the two independent reactions indicates that these reactions pass through a common intermediate. The isosbestic point at 335 nm is related to the Si—O bond formation, whereas the isosbestic point at 370 nm occurs due to the reductive process of naphthoquinone (path B of Scheme 1). The final products obtained from these reactions are diamagnetic (*vide* ESR) and no radical is observed during the course of these reactions. As both the reactions pass through a common intermediate, the favoured reaction mechanism in these cases is the one involving oxidative addition and reductive elimination (Scheme 1). In

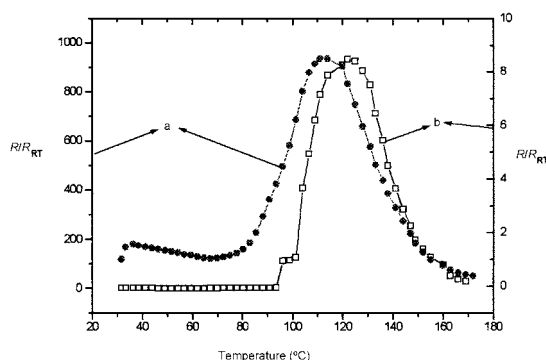


**Figure 2** Change in absorbance during the reaction of 1,4-naphthoquinone (0.1 mmol) with diphenylsilane (0.1 mmol) in the presence of  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  (0.01 mmol) in dichloromethane (3.5  $\text{cm}^3$ ) recorded at 4 min time intervals at 30 °C.



Scheme 1

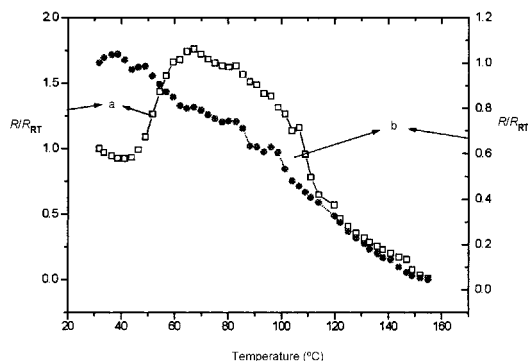
the naphthoquinone reduction reaction the absorption maximum at 333 nm is assigned to a charge transfer complex (**B**) that can be formed by interaction of partially reduced naphthoquinone with naphthalenediol, of which the latter is formed by reduction of a metal hydride species during the reaction. The charge transfer complex **B** can participate in the polymerization reaction. Thus,



**Figure 3** Plot of resistance  $R$  normalized to resistance at room temperature  $R_{RT}$  versus temperature of the siloxane prepared by  $\text{Pd(TMEDA)Cl}_2$  catalyst from the reaction of (a) 1,4-naphthalenediol and (b) 1,4-naphthoquinone with diphenylsilane.

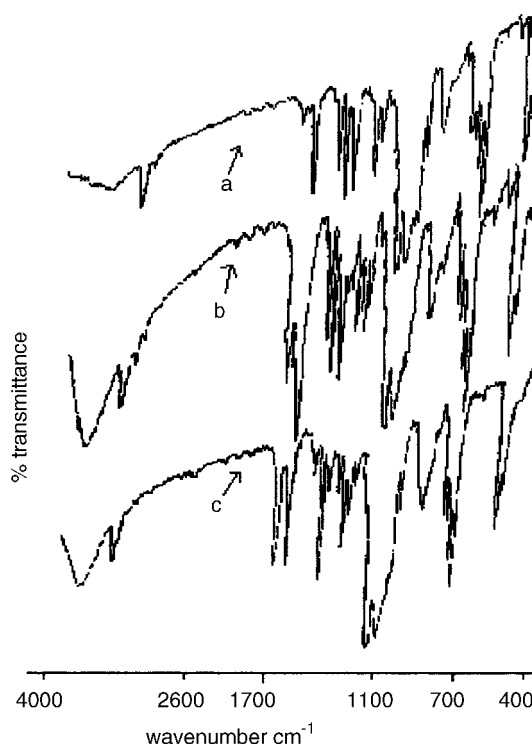
the pathways in these reactions are different than the pathways involved in the Ge—O bond-forming reaction by cross-coupling of germylene with quinonic compounds (where it occurs through radical mechanism).<sup>30</sup>

An intriguing feature of these oligomers is that siloxane films prepared by different catalysts have different shapes for variation of resistance versus temperature. The profiles obtained from each reaction are shown in Figs 3 and 4. As the temperature increases the resistance offered by the siloxane prepared by the  $\text{PdCl}_2$  catalyst decreases (Fig. 3b) continuously. It has a resistance versus temperature profile similar to a semiconductor. In the case of the  $\text{Pd(TMEDA)Cl}_2$  and  $\text{Pd(TEEDA)Cl}_2$  catalysts the resistance passes through a maximum with increase in temperature (Figs 3a and 4a). We defined the property of thermoelectric switching as one where a plot of resistance versus temperature has a normal Gaussian shape. Such properties were observed in systems having a combination of proton conductivity with inherent semiconducting properties, radical conductivity and structural changes around the metal ion.<sup>31–35</sup> Understanding such phenomena at the molecular level requires a thorough study on structure–property correlations. Moreover, the class



**Figure 4** Plot of resistance  $R$  normalized to resistance at room temperature  $R_{RT}$  versus temperature of the siloxane prepared from the reaction of 1,4-naphthoquinone with diphenylsilane by (a)  $\text{Pd(TEEDA)Cl}_2$  and (b)  $\text{PdCl}_2$  as catalyst.

of oligomers under consideration have  $sp^2$ -hybridized C—O bonds attached to silicon. These can impart delocalization in the system through involvement of  $d$ -orbitals of silicon as well as the lone pair of electrons on oxygen. These siloxanes are prepared from dehydrogenative coupling or reductive coupling reactions with the catalyst derived from the same metal. Thus, the difference in the resistance versus temperature plots of the films indicates the property originates from the environment of the metal ion. The IR spectra of siloxanes prepared from 1,4-naphthoquinone with diphenylsilane by  $\text{Pd(TMEDA)Cl}_2$  and  $\text{PdCl}_2$  have a clear difference in the regions  $3400$  and  $1680\text{ cm}^{-1}$  due to —OH stretching and overtone absorptions (Fig. 5a and b). The sample showing the property of thermoelectric switching possesses relatively higher intense absorptions at these positions, suggesting recognition/absorption of water in the interstices. A considerable decrease in the intensity of absorption peaks of **I** on heating to  $150\text{ }^\circ\text{C}$  (Fig. 5b and c) is observed. It is worth noting that a freshly prepared sample on heating to  $180\text{ }^\circ\text{C}$  does not show the same path of resistance versus temperature. Further proof of the loss of water molecules during heating from  $30$  to  $180\text{ }^\circ\text{C}$  is supported by thermogravimetry (TG), where the siloxanes prepared from 1,4-naphthoquinone and diphenylsilane by  $\text{PdCl}_2$ ,  $\text{Pd(TMEDA)Cl}_2$  and  $\text{Pd(TEEDA)Cl}_2$  have losses of weight of  $0\%$ ,  $1.5\%$  and  $3.7\%$  respectively. Differential scanning calorimetry (DSC) of the samples shows an endothermic process at the temperature where the resistance reaches maximum values. Thus the effect is attributed to the inclusion of water molecules in the interstices of the lattice.



**Figure 5** IR (KBr) spectra of siloxane prepared by (a)  $\text{PdCl}_2$  (b)  $\text{Pd(TMEDA)Cl}_2$ . (c) IR spectra of **I** heated to  $150\text{ }^\circ\text{C}$ .

The loss of a water molecule changes the environment around the palladium and results in a decrease in resistance from a limiting temperature. A change of co-ordination geometry of  $d^8$ -complexes has recently been used in a fluorescence thermometer device.<sup>36</sup> To obtain qualitative information on the geometrical change occurring around the palladium, a far-IR spectra of **I** was recorded at room temperature and after heating to  $200\text{ }^\circ\text{C}$ . In both cases there are strong absorptions at  $517$  and  $488\text{ cm}^{-1}$ , and this remains unchanged on heating. These bands are attributed to the Si—O framework on the basis of orthosilicate examples.<sup>37</sup> The only change observed is on a weak absorption appearing at  $418\text{ cm}^{-1}$ ; this absorption splits into two absorptions at  $418$  and  $405\text{ cm}^{-1}$ . This qualitatively supports the proposal of a change of co-ordination around palladium. Thus, it is believed that the irreversible effect of the thermoelectric switching property originates on the change of geometry around palladium, which is embedded in the siloxane network. Use of ethylenediamine controls the pore size in a supramolecular assembly of tin phosphates.<sup>38–40</sup> The cavity shapes and sizes in the

porous molecules are controlled by use of quaternary ammonium salts.<sup>39,40</sup>

The oligomers under consideration are thermally unstable. They decompose on heating, and a continuous weight loss in the region 180–800 °C is observed in each case. However, they have good thermal stability in the range 30–180 °C. The continuous weight loss indicates hydrolytic cleavage of Si—O bonds to give smaller molecular weight products.

In conclusion, new oligomers having provision for  $sp^2$  C—O bonds attached to silicon and possessing the property of thermoelectric switching are described.

## EXPERIMENTAL

The  $\text{PdCl}_2$  TMEDA, diphenylsilane, 1,4-naphthoquinone, and 1,4-naphthalenediols were obtained from Aldrich (USA) and were used without further purification. The IR spectra were recorded on a Nicolet-416 FT-IR spectrophotometer, the far-IR on a BOMEM DA-8 spectrophotometer, and the UV–visible spectra on a Hitachi U-2001 spectrophotometer; DSC and TG were undertaken using a Mettler Toledo Star system. The molecular weights of the oligomers were determined in THF using a Water GPC-HPLC-600 instrument. The  $^1\text{H}$  NMR were recorded on a Bruker 400 MHz NMR spectrometer. The resistance of the samples was measured on films made on a mica plate by using a set up comprising of a Hewlett Packard 34401 multimeter, a Keithley 6512 programmable electrometer and an Agronics 93-C DC power supply unit. The films were prepared by dissolving 2 mg of the oligomers in acetone ( $0.5\text{ cm}^3$ ) and then spreading over a mica plate with the aid of a capillary tube and drying by an air drier.

### Coupling reaction of 1,4-naphthoquinone with diphenylsilane by $\text{Pd}(\text{TMEDA})\text{Cl}_2$

A paste was made by mixing 1,4-naphthoquinone (79 mg, 0.5 mmol) with diphenylsilane (81 mg, 0.5 mmol) in a Schlenk tube and to this  $\text{Pd}(\text{TMEDA})\text{Cl}_2$  (9 mg 0.037 mmol) was added and put in an oil bath at 90 °C for 2 h. The black mass obtained was washed with hexane ( $3 \times 10\text{ cm}^3$ ) and the residue thus obtained was dried under vacuum; yield 46 mg (65%) of siloxane (I).  $^1\text{H}$  NMR ( $\text{CDCl}_3$ ) 6.2–8.4 (m, 58H), 1.8 (m, 16H). Elemental

analysis: Found: C, 70.45; H, 4.98. Calc. for  $\text{C}_{84}\text{H}_{74}\text{N}_2\text{O}_7\text{PdSi}_2$ : C, 70.09; H, 5.29%. Mass ( $m/z$ ) 1445–1437, 1352, 1237, 1154, 1098, 1075, 1016, 956, 937, 896, 878, 840, 814, 787, 758, 697, 676, 637, 619, 577, 559, 521. IR (KBr) 3360(bs), 1618(s), 1590(s), 1550(s), 1420(s), 1390(s), 1350(s), 1230(s), 1200(s), 1090(s), 1040(s), 870(bs), 720(s), 700(s), 680(s), 660(s), 480(s).

A similar reaction of 1,4-naphthoquinone with diphenylsilane in the presence of  $\text{PdCl}_2$  and  $\text{Pd}(\text{TEEDA})\text{Cl}_2$  gave to corresponding siloxanes in 32% and 40% yields respectively.

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